



**ULTRAPURE
MICRO 2020**

NOVEMBER 9 - 11 2020

YOUR GUIDE TO
THE ULTRAPURE MICRO 2020
VIRTUAL EVENT

FROM THE ORGANIZERS

Welcome to the first ever Ultrapure Micro 2020 Virtual Event!

Over the past 6 months, COVID-19 has changed the way we work and connect; we rely more than ever on our online connections to maintain relationships, share resources, and provide business continuity. This year, Ultrapure Micro has expanded its online presence in order to provide the much-needed space for conversations concerning micro contamination challenges in the semiconductor industry, culminating in what we hope will be an informative and interactive online event.

In September we launched the **Ultrapure Micro Platform**, featuring presentations from past conferences, data-rich and technical articles, industry news and more. This platform is the collaborative home of all the educational content that has been created over the last 30 years by industry experts, and with the help of the UPM community we hope that this online library will continue to grow. We encourage all conference attendees, who will have been provided with complimentary access, to check out the website to see how you can get involved and contribute to the UPM community.

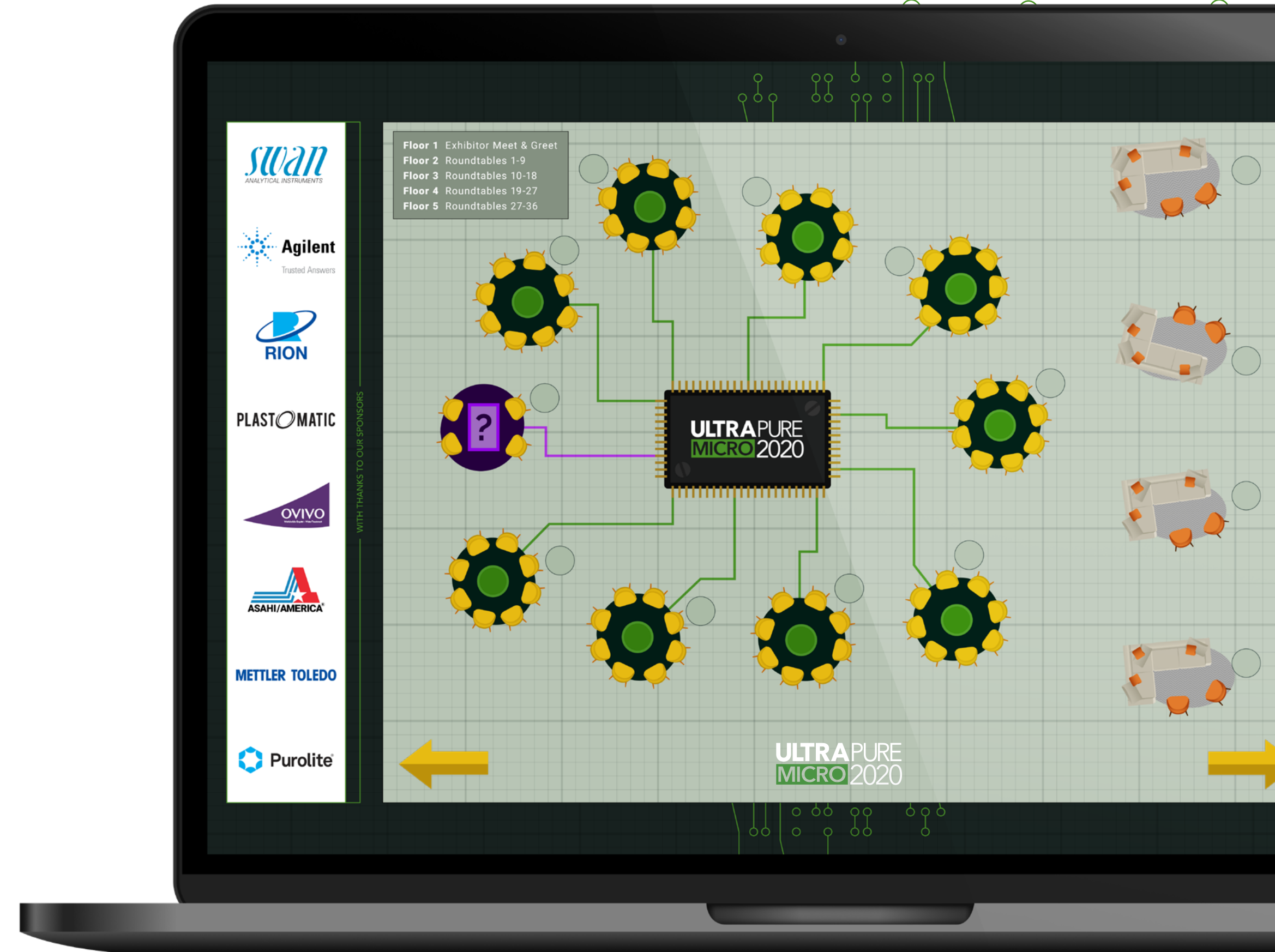
Since the postponement of the UPM conference, which was due to be held in May, we have also hosted a series of webinars concerning proactive technology management. These webinars have been free to attend, and have explored topics such as the tool environment, supply chain and material handling, as well as water management challenges. These webinars are an example of the type of topics and discussions that will be held at the virtual event, and so we encourage you all to **watch the recordings** on the Ultrapure Micro Platform.

As a culmination of these efforts, we will be ending the year with our first ever virtual event – this guide has been created to help you navigate the event technology and make the most of your time at UPM 2020. We very much enjoy meeting you all each year and so the Virtual Event will be highly interactive, allowing you to network, collaborate, and share with your peers in a safe environment.

We are delighted that you have chosen to join us for this special online event, and are available to answer your queries both prior to and during the virtual event.

Yours faithfully,

The UPM team



INTRODUCTION TO THE ONLINE EVENT

Ultrapure Micro 2020 will be held on November 9-11

Ultrapure Micro 2020 will be held on November 9-11, from 7:30 AM (PST) until 11:00 AM (PST), followed by extra networking time. We will be using a custom-designed platform which you can join using this link: <https://cvent.me/Ygx420>. This will also have been provided to you via email.

Logging in

To log in, please follow the link above. You will need to enter your first name, last name, and email. This must be the email you used to register for the conference. You will then be sent a verification code, which you must enter on the website page. Please note that this can take a minute or two to come through to your email inbox, or may even go to your junk folder.

You will now have entered the event site, where you can explore the event agenda, add sessions to your calendar, visit exhibitors and sponsors, as well as book appointments with them. This website is the main hub for the event, so please bookmark this page for the duration of the event, for ease of access.

The Agenda

With the help of our co-moderators we have curated an event which incorporates technical presentations, engaging roundtables, expert-led panel discussions and open networking sessions within a condensed period of time. As you can see from the agenda on pages 6, 7 and 8, the event has been divided into topic relevant sessions, meaning you can join for as little or as much time as you like, and you can listen to only the topics that are relevant to you whilst still managing your day to day responsibilities. Whilst keynotes and technical presentations will provide data-rich, viewable content, the interactive Q&A panels and roundtable sessions will provide the much-needed open collaboration and knowledge sharing that is offered at UPM every year. Presentations will not be available on demand until after the event, so please do check the agenda before the event.

These sessions can all be found in the agenda tab on the event website. Please note that this will be displayed in Pacific Standard Time – on the top right-hand side of the screen, you can change this to match your device time. On this agenda, you can find out more about the presenter, add the session to your calendar, and plan your participation in the event. To find out more about the roundtable sessions, please see page 5.

Sponsors and Exhibitors

Alongside the agenda, you will see two tabs for exhibitors and sponsors. Every sponsor and exhibitor will have a dedicated space where delegates can explore technical resources, send private messages, or have a live conversation through the video booth function. Our sponsors are there to help you with your manufacturing needs and will be happy to talk you through their most recent developments.

As well as having their booth, you will be able to meet the exhibitors during the roundtable and networking sessions. To find out more, see page 10.

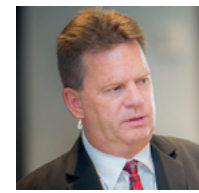
One-to-one Meetings

You are also able to book private meetings with our exhibitors and sponsors via the appointments module on the event homepage. You will automatically be provided with a meeting room, and the event can be exported to your calendar.

You can also use this to book one-to-one meetings with other delegates, however you must use your own video conferencing system. Anyone who opted out of being contacted by other delegates during registration will not be shown on this system.



THE CO-MODERATORS



Alan Knapp
Director, Microelectronics
Evoqua Water Technologies, LLC



Jim Snow
Senior Technologist
SCREEN SPE



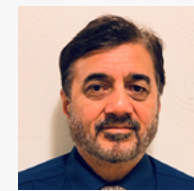
Dan Wilcox
Associate Principal | Process Engineering Dir.
Page/imes



Nora Colligan
Staff Engineer, Material Technology
Samsung Austin Semiconductor



Alex Milshteen
Facility Engineering Manager
Intel Corporation



Latif Ahmed
Microcontamination Engineer
Intel



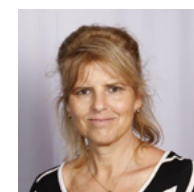
Don Hadder
Process Engineer
Intel



Rushi Matkar
Pathfinding Technologist
Ultrapure Water R&D Center, Intel



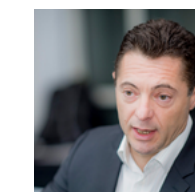
Bernie Zerfas
Facilities Engineer
GLOBALFOUNDRIES



Laura Ledenbach
Global Technical Quality Manager
PeroxyChem



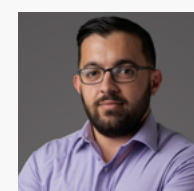
Glen Biggs
Facilities Engineer
GLOBALFOUNDRIES



Slava Libman
CEO
FTD Solutions LLC



Bob McIntosh
Consultant
Enviro-Energy Solutions



Mike Knapp
Facilities Engineer, PMP
Samsung Austin Semiconductor



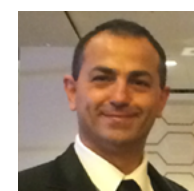
Tony Lachawiec
Formerly - Senior Process Engineer
Gas Systems Engineering, Intel



Walter Den
Professor, Water Resources Science & Tech.
Texas A&M University-San Antonio



César M. Garza
Staff Engineer
Samsung Austin Semiconductor



Nabil Mistkawi
Senior Staff Engineer/Technologist
Samsung Austin Semiconductor

EVENT TECHNOLOGY - FAQs

Will I need to download any programs or apps to participate in the Ultrapure Micro 2020 virtual event?

Ultrapure Micro 2020 will be hosted using browser-based platforms, meaning you will not need to download any programs or apps. However, you will need to use Google Chrome, Firefox, or Safari. If you use Internet Explorer or Microsoft Edge you will need to use a different browser in order to take part in the networking sessions. Our networking and Roundtable platform, Remo, is currently not fully supported on mobile phones or tablets so we advise you join on your computer or laptop. See *How do I participate in a roundtable session* to learn more about using Remo.

Our collaborative Q&A sessions will be hosted on GoToMeetings. This can be used in either desktop or browser versions. Please ensure that you have your company's permission to use this program.

Will I need a webcam and microphone?

Ultrapure Micro 2020 has been designed to be as interactive as possible, with numerous opportunities to connect with delegates, speakers, and sponsors in an environment which mimics an in-person conference. Therefore, we strongly encourage everyone to use their microphone and webcam throughout the event, to make the most of the networking sessions. If you do not have a webcam, you will still be able to speak with other attendees using the microphone only.

How do I participate in a roundtable session?

Roundtable sessions will be facilitated using a program called Remo. Remo is a browser-based networking platform which allows you to partake in small group discussions using both your webcam and microphone. If you would like to test the compatibility of your computer with our networking platform, please [click here](#) to test the connection.

Please note, **you will be required to register for Remo and log in separately**. Please register for Remo in advance by following [this link](#). You will then be invited to attend the different roundtable sessions. If you do not pre-register, you will still be able to join, but will need to create your account on the day. You will then be able to set up your profile and business card, which will help other attendees identify you. Once you have done this, you will have successfully set yourself up ahead of the event. We do recommend that you try and join the session early to complete these few tasks, so as not to miss the beginning of the session. A link to the roundtable session will be provided within the agenda section of the online event platform.

- Once you join the event, you will be prompted to turn your microphone and webcam on, before being automatically placed at a random table. There may be other people sat at this table when you join.
- There are several "floors" on Remo. This means that each floor has a different set of roundtable topics and hosts. To change floors, you will need to use the numbered buttons on the left of your screen.
 - **Floor 1** - Exhibitor Meet & Greet
 - **Floor 2** - Roundtables 1-9
 - **Floor 3** - Roundtables 10-18
 - **Floor 4** - Roundtables 19-26
 - **Floor 5** - Roundtables 27-36
- All roundtables are numbered. In this brochure (page 8) you will find a list of roundtables with their allocated number. To join a roundtable, please double click the corresponding table within the Remo platform. There is a limit of 8 people at each table, including your host. If you are not able to join your first table of choice, please join another topic – this is a first come first serve system. On each day, there will be two rotations of these tables, so if you are not able to join a table first time, you will have another chance to do so.
- At the top of the screen you will see a timer. When prompted, please find the next roundtable you wish to join and double click to enter.
- If you click on any of the other attendees, you will be able to see their business card. To edit your own business card / Remo profile after you have registered on the platform, click the letter of your first name which will appear in the top right corner, and press 'Edit Profile'. Please include your full name, organization, and job title. If you can also add an image of your company logo as your profile picture, this will be very useful for helping other attendees find you in the networking room. You may upload a picture of yourself if you prefer.
- Remo also has a chat function. Using this you will be able to talk to other attendees without having to be on their table.

AGENDA - DAY ONE MONDAY 9TH NOVEMBER (PST)

6.45am – 7.30am	Exhibitor Live Booths open				
7.30am – 7.40am	Welcome Address and Best Presentation Awards 2019				
7.40am – 8.20am	Keynote: IRDS: Devices and Systems Innovation in the Next 15 Years Paolo Gargini , Chairman, IRDS				
8.20am – 8.25am	Introduction to the technical sessions				
8.25am – 8.30am	Transition Break				
	Wafer Contamination Control – Particles Monitoring	UPW Process Optimization	Water and Resources Conservation	Airborne Molecular Contamination (AMC) and High Purity Gases Control	
8.30am – 8.45am	Microanalysis: A novel method to characterize and speciate contaminants in Ultra Pure Water (UPW) and other aqueous chemicals Ashutosh Bhabhe , Entegris	Determine functional pore sizes of ultrafiltration membranes by nanoparticle retention test using single particle ICP-MS Qilin Chan , 3M	Resource Conservation Projects at GLOBALFOUNDRIES Fab8 in Malta, New York Thomas Huang , GLOBALFOUNDRIES	A Retrospective Review of AMC Issues: Our Understanding and Issues Incurred Walter Den , Texas A&M University-San Antonio <i>Co-authoring organization: Samsung Austin Semiconductor</i>	
8.45am – 9.00am	Particle analysis of unpatterned wafers with UNISERS Ali Altun , UNISERS	Leveraging Advanced Analytical Techniques and Productive Data Processing Tools to Address UPW Challenges Gil Maron , FTD Solutions	Smart primary wastewater management – Strategies, rules, examples Jochen Ruth , Pall <i>Co-authoring organization: RBFM Consulting</i>	Comprehensive Online AMC Analysis Using SIFT-MS Helena Barnes , Syft Technologies	
9.00am – 9.15am	Yield Enhancement in Wet Cleaning of Silicon Wafers by Critical Area Analysis Drew Sinha , Sinha Solutions <i>Co-authoring organization: Slava Libman, FTD Solutions</i>	Can Nanoparticles penetrate UPW polishing resins? Nanoscale particle interactions by high resolution imaging of single resin beads Maria Pia Herrling , Ovivo <i>Co-authoring organization: Karlsruhe Institute of Technology</i>	Construction of a new wastewater recovery system / business model Tanaka Yu , KURITA WATER INDUSTRIES	The challenges of Improving Sensitivity and Speed of Response for Detecting Airborne Molecular Contaminants in Cleanrooms Florian Adler , Tiger Optics	New sampling module for ultra-low level cation, anions, and organic acids in air/gases Maohua Pan , Air Liquide Electronics
9.15am – 9.45am	Q&A Panel with Speakers	Q&A Panel with Speakers	Q&A Panel with Speakers	Q&A Panel with Speakers	
9.45am – 9.55am	Transition Break				
9.55am - 10.00am	Introduction to Remo and the Roundtable Session				
10.00am – 10.55am	Roundtables				
10.55am – 11.25am	Open Networking				

AGENDA - DAY TWO TUESDAY 10TH NOVEMBER (PST)

6.45am – 7.30am	Exhibitor Live Booths open			
7.30am – 7.35am	Welcome Remarks			
7.35am – 8.20am	Keynote: Semiconductor Market Trends - Optimistic Uncertainty of 2020 and Beyond Dave Anderson , President, SEMI Americas			
8.20am – 8.25am	Introduction to the Technical Sessions			
8.25am – 8.30am	Transition Break			
	Critical Particle Monitoring	UPW System Improvement	Wastewater Treatment	Contamination Control in Liquid Chemicals
8.30am – 8.45am	Measurement of Particle Precursors in Ultrapure Water Gary van Schooneveld , CT Associates	Risks incurred by morphology change of silica in ion exchange resins and their countermeasures Atsushi Miramatsu , KURITA WATER INDUSTRIES	Durability improvement of fluoride ion sensor against hydrogen peroxide in wastewater management Takamasa Kinoshita , HORIBA Co-authoring organization: Samsung Austin Semiconductor	Effects of Static Electricity on Voltage-sensitive Metrology for Chemical Delivery Systems Michael Perkins , Mega Fluid Systems
8.45am – 9.00am	Fundamentals of Acoustic Particle Counting and Validation for UPW Monitoring Najib Alia , Ovivo	Endotoxin Reduction in UPW Majid Entezarian , 3M	Biological Point of Use Wastewater Treatment Joerg Winter , DAS Environmental Expert	When Should Skew Corrected Control Limits be Updated? Thomas Bzik , Versum Materials
9.00am – 9.15am	Development and Evaluation of a 3 nm Ultrapure Liquid Quality Monitor Derek Oberreit , Kanomax FMT	Approaching UPW System Management and Design in a Systematic Way Joshua Best , FTD Solutions, and Jesica Beccue , CMC Materials	Hydrofluoric Acid Neutralization and Precipitation Utilizing High Performance Lime Narahari Kramadhati , Lhoist Co-Authors: Luke Wilson and Stephanie Lopez, Samsung Austin Semiconductor	Method Development for Trace Impurities in Novel Sub-nm Photoresists by Inductively Coupled Plasma Mass Spectrometry (ICP-MS) Mohsina Islam , ChemTrace, A Business Unit of UCT
9.15am – 9.45am	Q&A Panel with Speakers	Q&A Panel with Speakers	Q&A Panel with Speakers	Q&A Panel with Speakers
9.45am – 9.55am	Transition Break			
9.55am - 10.00am	Introduction to Remo and the Roundtable Session			
10.00am – 10.55am	Roundtables			
10.55am – 11.25am	Open Networking			

AGENDA - DAY THREE WEDNESDAY 11TH NOVEMBER (PST)

6.45am – 7.30am	Exhibitor Live Booths open			
7.30am – 7.35am	Welcome Remarks			
7.35am – 8.20am	<p>Panel Discussion: IRDS Yield Enhancement Panel: discussing the importance and the process of the contamination control roadmap development</p> <p>Moderator: Slava Libman, CEO, FTD Solutions</p> <p>Panelists:</p> <p>Bob McIntosh, Enviro Energy Solutions</p> <p>Christoph Hocke, Infineon</p> <p>Andreas Neuber, Applied Materials</p> <p>Dan Wilcox, Page/imes</p> <p>Nabil Mistkawi, Samsung Austin Semiconductor</p> <p>Don Hadder, Intel Corporation</p>			
8.20am – 8.25am	Introduction to the Technical Sessions			
8.25am – 8.30am	Transition Break			
	UPW Contamination Control	UPW and Liquid Chemicals System Improvements	Water Management in Cooling Systems	Wastewater Treatment and Environmental Compliance
8.30am – 8.45am	<p>Understanding Nanoparticle Contamination in Ultrapure Water Generation and Distribution</p> <p>Dan Rodier, Particle Measuring Systems and</p> <p>Glen Slayter, Intel Corporation</p>	<p>New quartz glass – electric melting of a synthetic “grain” in an inert atmosphere with high, non-removable OH content in the glass structure – tailored for 185nm ultrapure water applications</p> <p>Klaus Zoltner, Heraeus</p>	<p>Condensor Loop Best Known Methods</p> <p>Alex Evashenk, FTD Solutions</p>	
8.45am – 9.00am	<p>Trace metal analysis (ppq level) in ultrapure water using Monolith as an ion concentrator</p> <p>Kyohei Tsutano, ORGANO</p>	<p>Thermoplastic pipe stress modelling – Best Known Methods (BKM’s) for safe and reliable long-life Double Containment Piping Systems</p> <p>Hanspeter Mueller, George Fischer Piping Systems. Co-authoring organization: Semtec Inc.</p>	<p>Rapid Detection of Biofouling in Cooling Water Systems</p> <p>Philip Yu, Nalco</p>	<p>Managing the Biocide Measurement, Control & Regulatory Challenges in Wastewater Dichlorination and Disinfection using online TRO (Total Residual Oxidant)</p> <p>Jiawei Zhang, Thermo Fisher Scientific</p>
9.00am – 9.15am	<p>Removal of trace metals from Ultra Pure Water (UPW) using membrane-based solutions</p> <p>Sid Sampath, Entegris</p>	<p>Best Practice in the Design and Fabrication of Fluoropolymer-lined vessels as reliable Ultra-High Purity Fluid containment systems: Influence of material selection, fabrication methods on tank performance</p> <p>Steve Rau, Edlon</p>		<p>Options to manage PFAS compounds in wastewater: A Reverse Osmosis/Membrane perspective</p> <p>Juan Zepeda, Suez Water Technologies and Solutions</p>
9.15am – 9.45am	Q&A Panel with Speakers	Q&A Panel with Speakers	Q&A Panel with Speakers	
9.45am – 9.50am	Transition Break			
9.50am - 10.00am	Closing Remarks			
10.00am – 11.00am	Open Networking			

ROUNDTABLES

To navigate between floors on Remo, use the numbered buttons on the left-hand side of the screen. Whilst Floor 1 acts as the Exhibitors Area, Floors 2-5 will contain the hosted roundtables, as below. Each roundtable has a number, which will match table number within the Remo platform. To join a table, double click on it. There is a maximum of 8 people per table, host included, and this is a first come first serve system. There will be 2 rotations of roundtables on each day.

FLOOR 2	FLOOR 3	FLOOR 4	FLOOR 5
<p>Roundtable 1 – Key Lessons and Considerations in UPW and HUPW Distribution Shutdown and Restart James Lee, Samsung Austin Semiconductor</p>	<p>Roundtable 10 – Design for Maintenance & Operation Principles in UPW Systems – End User Perspective Alana Denning, Page/imes</p>	<p>Roundtable 19 – New Challenges of Specialty Waste Treatment Systems Alan Knapp, Evoqua</p>	<p>Roundtable 27 – AMC Metrology Peng Sun, ChemTrace, A Business Unit of UCT</p>
<p>Roundtable 2 – Ion Exchange Resin Management: Lifetime, Triggers, Operations, Strategy Varinder Malik, Samsung Austin Semiconductor</p>	<p>Roundtable 11 – Ultrapure Water Sequences – What's on second? Chuck Dale, Suez</p>	<p>Roundtable 20 – Best Practices for POU Scrubber Wastewater Management Zachary Boswell, Samsung Austin Semiconductor</p>	<p>Roundtable 28 – AMC – Fab & Tool Environment Walter Den, Texas A&M University-San Antonio</p>
<p>Roundtable 3 – UPW Sampling and Lab Testing: How Often, Which Samples, What Parameters, Methods? Maohua Pan, Air Liquide Electronics</p>	<p>Roundtable 12 – The impact of over stated tool requirements on fab support system design FTD Solutions</p>	<p>Roundtable 21 – Fab tool water optimization and reclamation Jim Snow, SCREEN SPE</p>	<p>Roundtable 29 – AMC – FOUP & Mini-Environment Latif Ahmed, Intel</p>
<p>Roundtable 4 – Next Generation Particle Metrology for UPW for Particle Pre-Cursor Measurement Gary Van Schooneveld, CT Associates</p>	<p>Roundtable 13 – Chemicals – Sampling and Analysis of in-line and end-of-line Ultra High Performance Chemicals Florian Adler, Tiger Optics</p>	<p>Roundtable 22 – Instrumentation Selection in Wastewater Victoria Yun, Samsung Austin Semiconductor</p>	<p>Roundtable 30 – Critical Component Analysis Surjany Russell, ChemTrace, A Business Unit of UCT</p>
<p>Roundtable 5 – New Challenges to Ultrapure Water Filtration Jochen Ruth & Gerd Hesser, Pall</p>	<p>Roundtable 14 – Ultra High Performance Chemical Distribution and Blending David Kandiyeli, Mega Fluid Systems</p>	<p>Roundtable 23 – SEMI C98 – Guide for Treatment of Reuse Water in Semiconductor Processing Paul Kerr, Intel</p>	<p>Roundtable 31 – Filter Rating and Testing – What does it mean? Ryan Pavlick, Intel</p>
<p>Roundtable 6 – Physics of the particle vs. high-molecular-weight dissolved organic Steve Kosier, Kanomax FMT</p>	<p>Roundtable 15 – Chemicals – Supply Chain Challenges and the Cost of Quality Archita Sengupta, Intel</p>	<p>Roundtable 24 – Selection of Piping Materials for Wastewater Collection Systems and Hydrogen Peroxide in Wastewater Casey Williamson, Semtec</p>	<p>Roundtable 32 – Prefabrication Preassembly Modularization and Offsite Fabrication: The IKEA Concept John Painter, Pure Facilities Solutions</p>
<p>Roundtable 7 – “Real” Particle Concentration in UPW Unknown? Discussion on different state of the art particle metrologies Maria Pia Herrling, Ovivo</p>	<p>Roundtable 16 – Filtration for UHP Chemicals – Which filter is which and where do I use it? Ashutosh Bhabhe, Entegris</p>	<p>Roundtable 25 – HF treatment – Lime or CaCl₂ - which is best for me? Luke Wilson & Stephanie Lopez, Samsung Austin Semiconductor</p>	<p>Roundtable 33 – Operations in the time of Pandemic Brad Herbert, ON Semiconductor</p>
<p>Roundtable 8 – Evaluating UPW System Capacity and Minimizing Upgrade Scope Dave Buesser, FTD Solutions</p>	<p>Roundtable 17 – High Purity Chemicals for Advanced Technology Kevin Prettyman, GLOBALFOUNDRIES</p>	<p>Roundtable 26 – Azoles Treatment Mikael Khan, Arvia Technology</p>	<p>Roundtable 34 - H₂O₂ in Wastewater – When do I need to worry? FTD Solutions</p>
<p>Roundtable 9 – What is new in UPW membrane technology? Denise Haukkala, DuPont</p>	<p>Roundtable 18 – Chemical Particles <20nm: How to pick the right filter and detection challenges Anthony Ozzello, Entegris</p>		

EXHIBITORS AND SPONSORS

We are extremely grateful for all the support from our 2020 sponsors and exhibitors, all of whom are keen to meet you at their virtual booths! On the main event platform, each will have a dedicated exhibit space where delegates can explore technical resources, send private messages, leave their business card or have a live conversation through the video booth function. Delegates will have 24/7 access to these pages, but we advise everyone to visit the live video booths sometime between 6.45am and 9.45am each day, to try and catch a company representative. They will be happy to speak with you about what who they are, what they do, and what their company has been working on in the past year. If you don't catch them then, either leave a message, or book your own one-to-one meeting at a time that best suits you, via the appointments module on the front page.

You will also have the chance to meet our sponsors and exhibitors during the roundtable and networking session. In the networking platform, exhibitors will host tables for meet & greets on the First Floor.

To make sure you reach everyone, check in each day, as the sponsors and exhibitors will rotate – you can see who will be available on which day in the table to the right. Delegates, speakers, sponsors and exhibitors will all be on Remo together, and so all kinds of interactions and conversations will be taking place.

Industry Partners



Day One – Monday 9th November

NETWORKING LOUNGES SPONSORED BY



MEET & GREET TABLES



Day Two – Tuesday 10th November

NETWORKING LOUNGES SPONSORED BY



MEET & GREET TABLES





ULTRAPURE MICRO PRIZE DRAW

In this year's prize draw, we will be giving away a pair of **Apple AirPods**, an **Amazon Echo Dot**, and a **Roomba**!

To be in with a chance of winning any of these three items, all you need to do is score 500 points by completing the following tasks – you can do each of these more than once. The winners will be announced after the event via the Ultrapure Micro Platform.

Add a session to your calendar	+5 points
View an exhibitor's profile	+10 points
Click on an exhibitor's weblink	+10 points
Join an agenda session	+10 points
Open an exhibitor's document	+20 points
Leave your details at an exhibitor booth	+30 points
Fill in our feedback survey	+30 points
Join virtual exhibitor booth	+40 points
Attend an appointment with an exhibitor	+50 points

Unfortunately you will not be able to see your score on the platform, but if you reach out to **Isabel Brull** (isabel.brull@globalwaterintel.com) she can update you on your score during the event.



THANK YOU TO ALL THE UPM SPONSORS AND EXHIBITORS!